mode in reactions of  $V^{3+, 11, 12}$  It is interesting to note that  $\Delta S^{\pm}$  is  $-11 \pm 4$  eu at 100° for Fe(DMSO)<sub>6</sub><sup>3+</sup> exchange and -16 eu for Ni(DMSO)62+ DMSO exchange.<sup>5</sup>  $V(DMSO)_6^{3+}$  should be especially interesting.

(11) W. Kruse and D. Thusius, *Inorg. Chem.*, 7, 464 (1968).
(12) B. R. Baker, N. Sutin, and T. J. Welch, *ibid.*, 6, 1948 (1967).

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## Dihalocarbene Insertions into Optically Active R<sub>3</sub>Si\*H with Retention of Configuration<sup>1</sup>

Sir:

Recently there has been much interest in carbene (or carbenoid) insertions into Si-X bonds in which X =H,<sup>2</sup> C (ring strained),<sup>3</sup> and Cl.<sup>4</sup> We wish to report the first stereochemical studies on such insertions, using optically active α-naphthylphenylmethylsilane, R<sub>3</sub>Si\*H.<sup>5</sup> Specifically, the present work involved insertion of CCl<sub>2</sub> and CBr<sub>2</sub> using the appropriate organomercury compounds, trichloromethyl- and tribromomethylphenylmercury, PhHgCX<sub>3</sub>.<sup>6</sup> The general procedure comprised refluxing a 200-ml benzene solution of the silane (40 mmol) and organomercury compound (40 mmol). Reaction times were 24 hr for PhHgCCl<sub>3</sub> and 4 hr for PhHgCBr<sub>3</sub>. The phenylmercuric halide which formed was filtered, the solvent removed by distillation, and the crude product taken up in CCl<sub>4</sub> solvent. Unreacted R<sub>3</sub>Si\*H in the crude product was converted to R<sub>3</sub>Si\*OH by treatment with Cl<sub>2</sub> followed by hydrolysis of the Si-Cl bond, and the product was then passed through a column of silica gel for removal of the R<sub>3</sub>Si\*-OH. This procedure gave  $R_3Si^*CHX_2$  of good purity as determined by infrared and nmr spectra and analysis for C, H, and X. Using dextrorotatory R<sub>3</sub>Si\*H the insertions proceeded as follows.

$$(+)-R_{3}Si^{*}H + PhHgCX_{3} \longrightarrow (+)-R_{3}Si^{*}CHX_{2}$$

$$[\alpha]D + 35.0^{\circ} \qquad X = Cl; \ [\alpha]D + 21.0^{\circ}$$

$$X = Br; \ [\alpha]D + 14.3^{\circ}$$

The problem of correlation of configuration between R<sub>3</sub>Si\*H and R<sub>3</sub>Si\*CHX<sub>2</sub> was overcome by preparation of the insertion products via independent syntheses involving reactions of known stereochemistry. The latter used organolithium reagents in coupling reactions with R<sub>3</sub>Si\*Cl, a class of reactions known to proceed with inversion of configuration.7 The dichloromethyllithium reagent was prepared in THF solvent by the general low-temperature method pre-

(1) Current support of this work by the National Science Foundation (1) Current support of this work by the National Science Foundation is gratefully acknowledged. Initial studies were carried out at The Pennsylvania State University with support from Dow Corning Corp.
 (2) D. Seyferth and J. M. Burlitch, J. Am. Chem. Soc., 85, 2667
 (1963); K. A. Kramer and A. N. Wright, J. Chem. Soc., 3604 (1963).
 (3) D. Seyferth, R. Damrauer, and S. S. Washburne, J. Am. Chem. Soc., 89, 1540 (1967).
 (4) K. A. W. Kramer and A. N. Wright, Angew. Chem., 74, 468
 (1962)

(1962).

(5) L. H. Sommer and C. E. Frye, J. Am. Chem. Soc., 81, 1013 (1959); L. H. Sommer, C. L. Frye, G. A. Parker, and K. W. Michael, ibid., 86, 3271 (1964).

(6) It has been emphasized previously by Seyferth and coworkers that the use of  $PhHgCX_3$  for  $CX_2$  insertion into SiH comprises an especially useful method which avoids strong bases that can give nucleophilic substitution with Si-H bonds.

(7) For recent numerous examples, see: L. H. Sommer, W. D. Korte, and P. G. Rodewald, J. Am. Chem. Soc., 89, 862 (1967).

viously reported for  $\alpha$ -chloroalkyllithium compounds.<sup>8</sup>

$$(-)-R_{3}Si^{*}H + Cl_{2} \xrightarrow{\text{retention}} (+)-R_{3}Si^{*}Cl \xrightarrow{\text{inversion}}_{-90^{\circ}} \\ [\alpha]D - 35.2^{\circ} \qquad [\alpha]D + 6.3^{\circ} \xrightarrow{\text{LiCHX}_{2}}_{-90^{\circ}} \\ (+)-R_{3}Si^{*}CHX_{2} \\ X = Cl; \ [\alpha]D + 22.6^{\circ} \\ X = Br; \ [\alpha]D + 13.8^{\circ} \end{bmatrix}$$

Dibromomethyllithium was prepared by the reaction of dichloromethyllithium with dibromomethane9 in THF solvent. Thus based on assignment of an inversion stereochemistry to the coupling reactions of LiCHX<sub>2</sub> with  $R_3Si^*Cl$ , (+)- $R_3SiCHCl_2$  and (+)- $R_3Si^*$ -CHBr<sub>2</sub> have the same configuration as (+)-R<sub>3</sub>Si\*H and the insertion of CCl<sub>2</sub> and CBr<sub>2</sub> into the silicon-hydrogen bond proceeds with retention of configuration. The solid R<sub>3</sub>Si\*CHCl<sub>2</sub> from the coupling reactions was recrystallized up to constant rotation,  $[\alpha]D + 24.4^{\circ}$ , indicating optical purity. From this it appears that the insertion proceeded with a high degree of stereospecificity,  $\sim 93\%$ .

The insertion products of R<sub>3</sub>Si\*H and those obtained by coupling reactions of LiCHX<sub>2</sub> with R<sub>3</sub>Si\*Cl had identical infrared and nmr spectra.

The present finding of a retention stereochemistry for the insertion reactions of CCl<sub>2</sub> and CBr<sub>2</sub> with R<sub>3</sub>Si\*-H is certainly consistent with a three-center mechanism involving direct electrophilic attack of CX2 on the silicon-hydrogen bond (I). It is interesting to note that a very similar mechanism (II) has been advanced previously<sup>10</sup> for the reactions of  $R_3Si^*H$  with  $X_2$ (X = Cl or Br) which also proceed with retention of configuration. These reactions were postulated to involve electrophilic attack on R<sub>3</sub>Si\*H by X<sup>+</sup>. Transition states I and II both involve attack of electrophilic



species on the silicon-hydrogen bond,<sup>11</sup> and both proceed with retention of configuration.

(8) D. F. Hoeg, D. I. Lusk, and A. L. Crumbliss, ibid., 87, 4147

(a) D. F. Hoeg, D. I. Lusk, and A. L. Crumbins, *bia*, 87, 4147 (1965). Our procedure employed – 90° instead of – 100° as reported.
(9) G. Köbrich, *Angew. Chem. Intern. Ed. Engl.*, 6, 41 (1967).
(10) L. H. Sommer, "Stereochemistry, Mechanism and Silicon," McGraw-Hill Book Co., Inc., New York, N. Y., 1965, pp 107–109.

(11) In many respects dihalocarbenes behave as electrophilic species. For a summary see: W. Kirmse, "Carbene Chemistry," Academic Press Inc., New York, N. Y., 1964, pp 163-164. Also recent evidence indicates that  $PhHgCX_3$  functions as a source of free  $CX_2$  carbene: D. Seyferth, J. Yick-Pui Mui, and J. M. Burlitch, J. Am. Chem. Soc., 89, 4953 (1967).

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## A Distinctly Bent Metal-Nitrosyl Bond. The Preparation and Structure of Chlorocarbonylnitrosylbis(triphenylphosphine)iridium Tetrafluoroborate, $[IrCl(CO)(NO)(P(C_6H_5)_3)_2][BF_4]$

## Sir:

We wish to report the first accurately documented example of a distinctly bent M-N-O linkage in a metal nitrosyl complex and to present an explanation for this unusual mode of bonding.